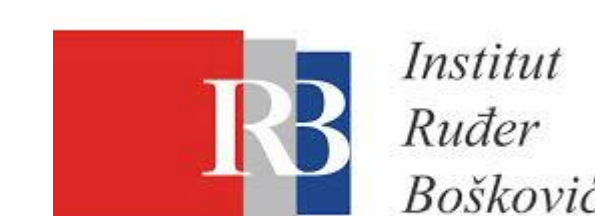




Photodetectors and LEDs based on $\beta\text{-Ga}_2\text{O}_3$ membranes obtained by ion-beam-assisted exfoliation

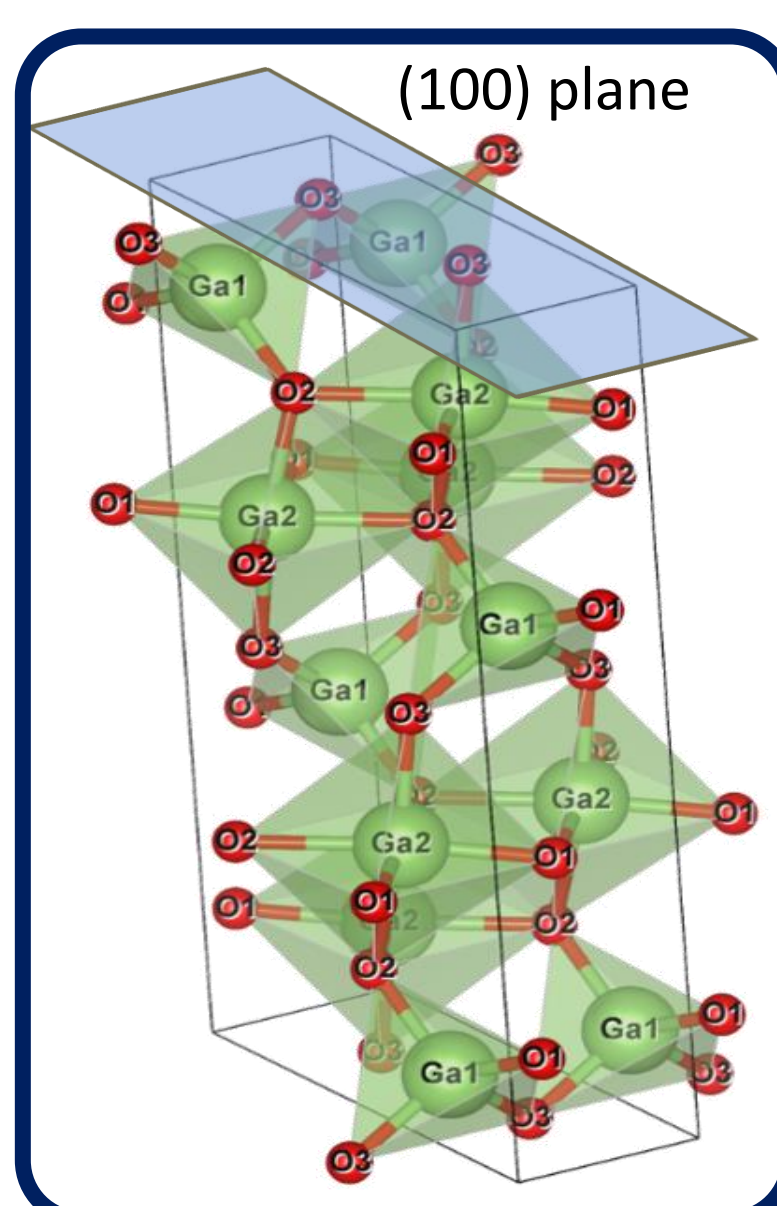
PHD IN NUCLEAR TECHNOLOGIES AND SCIENCES

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Gallium Oxide ($\beta\text{-Ga}_2\text{O}_3$)

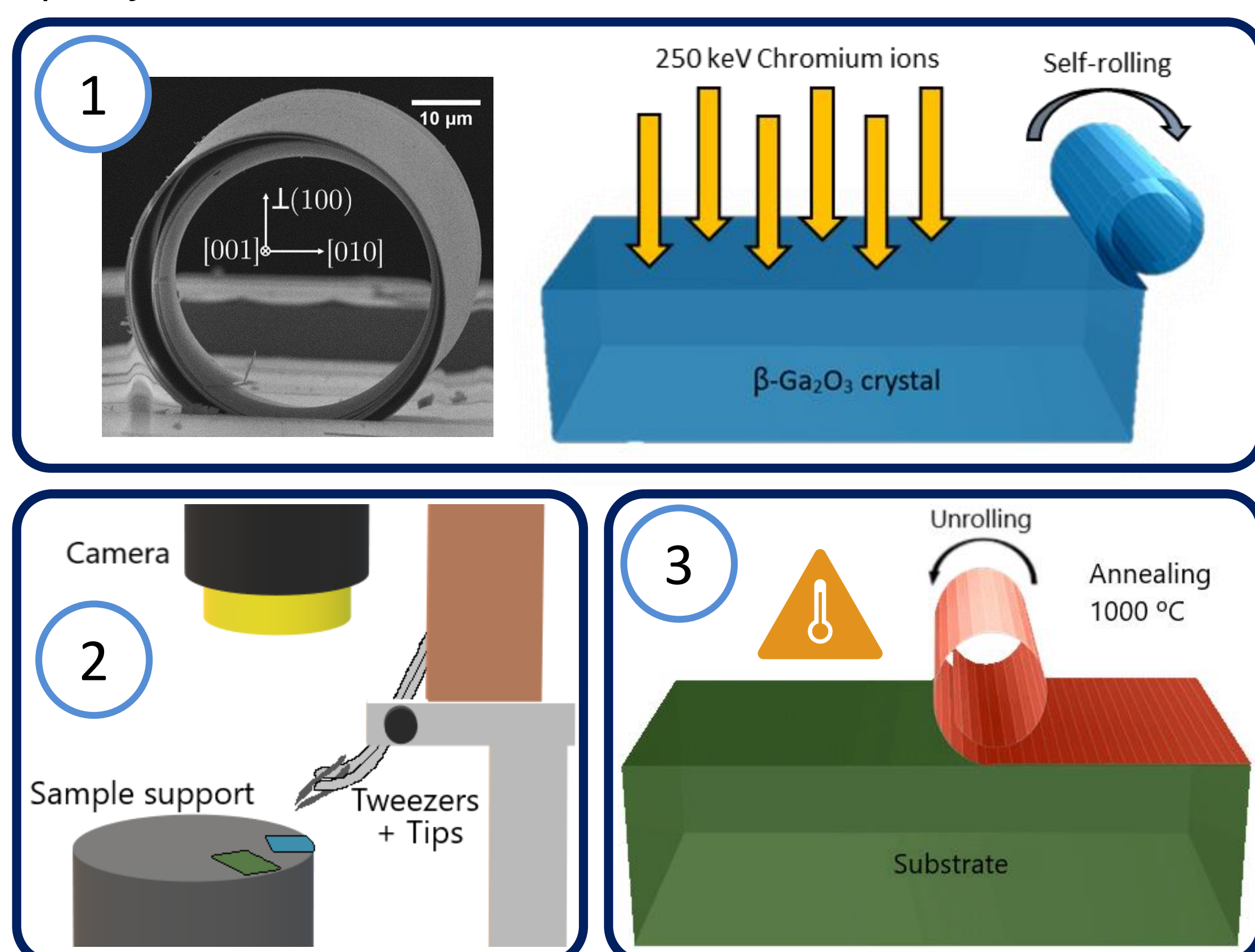
- $\beta\text{-Ga}_2\text{O}_3$ is a **semiconductor** studied for different applications, such as deep ultraviolet photodetectors;
- It has a **wide bandgap** of ~ 4.8 eV, naturally tuned to wavelengths **<260 nm**, making it ideal for **solar-blind optoelectronics**;
- High responsivity** (R) and **detectivity** (D^*) are reported for a variety of device geometries and fabrication techniques;
- Easy cleavage** along its (100) plane, so **mechanical exfoliation** of membranes is commonly employed;
- Low thermal conductivity and only n-type doping.



Ion-beam-induced exfoliation

- Ion implantation** (1) (ex.: 250 keV Cr^{2+} ions), on an (100) plane oriented $\beta\text{-Ga}_2\text{O}_3$ crystal, causes a thin layer (~ 300 nm) to self-roll into microtubes;
- A pick-and-place technique is used to **transfer** (2) these tubes to a **substrate of choice**: transparent, p-type, high thermal conductivity, etc...;
- Rapid thermal annealing for 60 s at 900 °C in N_2 atmosphere is used to **unroll the tubes** (3) and recover the implantation defects, resulting in high crystalline quality membranes on the new substrate.

Membrane preparation



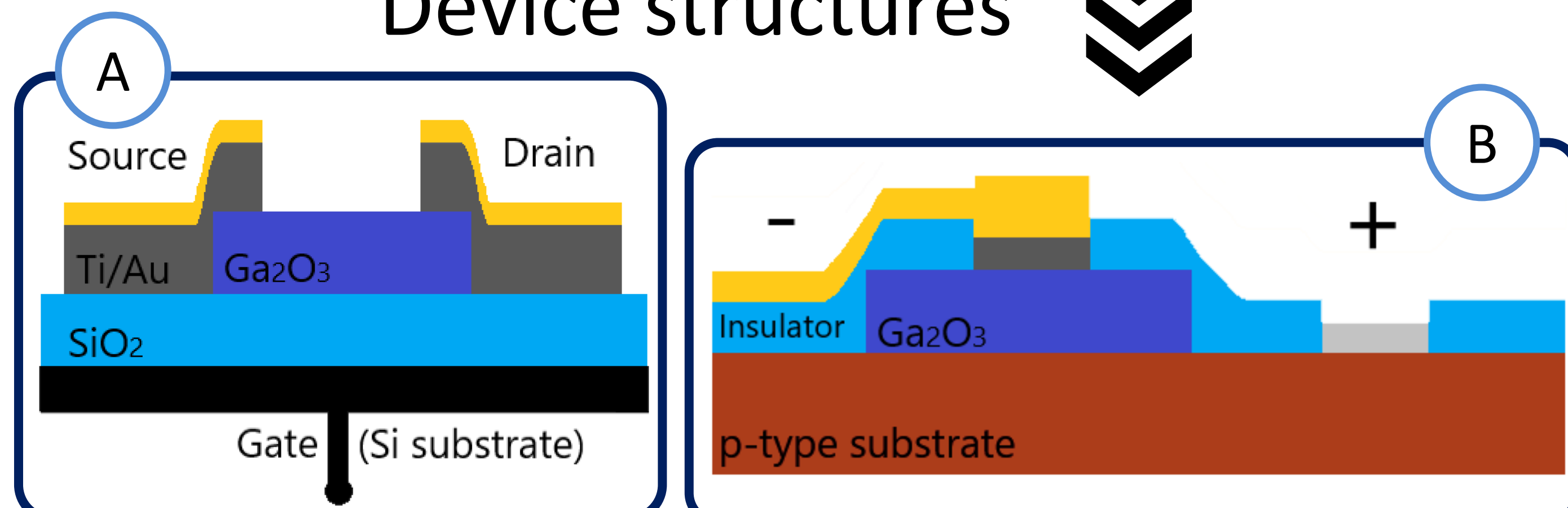
Device fabrication

The objective of this project is to use these membranes to develop several optoelectronic devices:

- Metal-semiconductor-metal (**MSM**) **photodetectors** and **phototransistors**, sharing structure (A), have been tested;
- p-n heterojunctions** and **light-emitting diodes (LEDs)**, sharing structure (B), are to be developed during the PhD project.

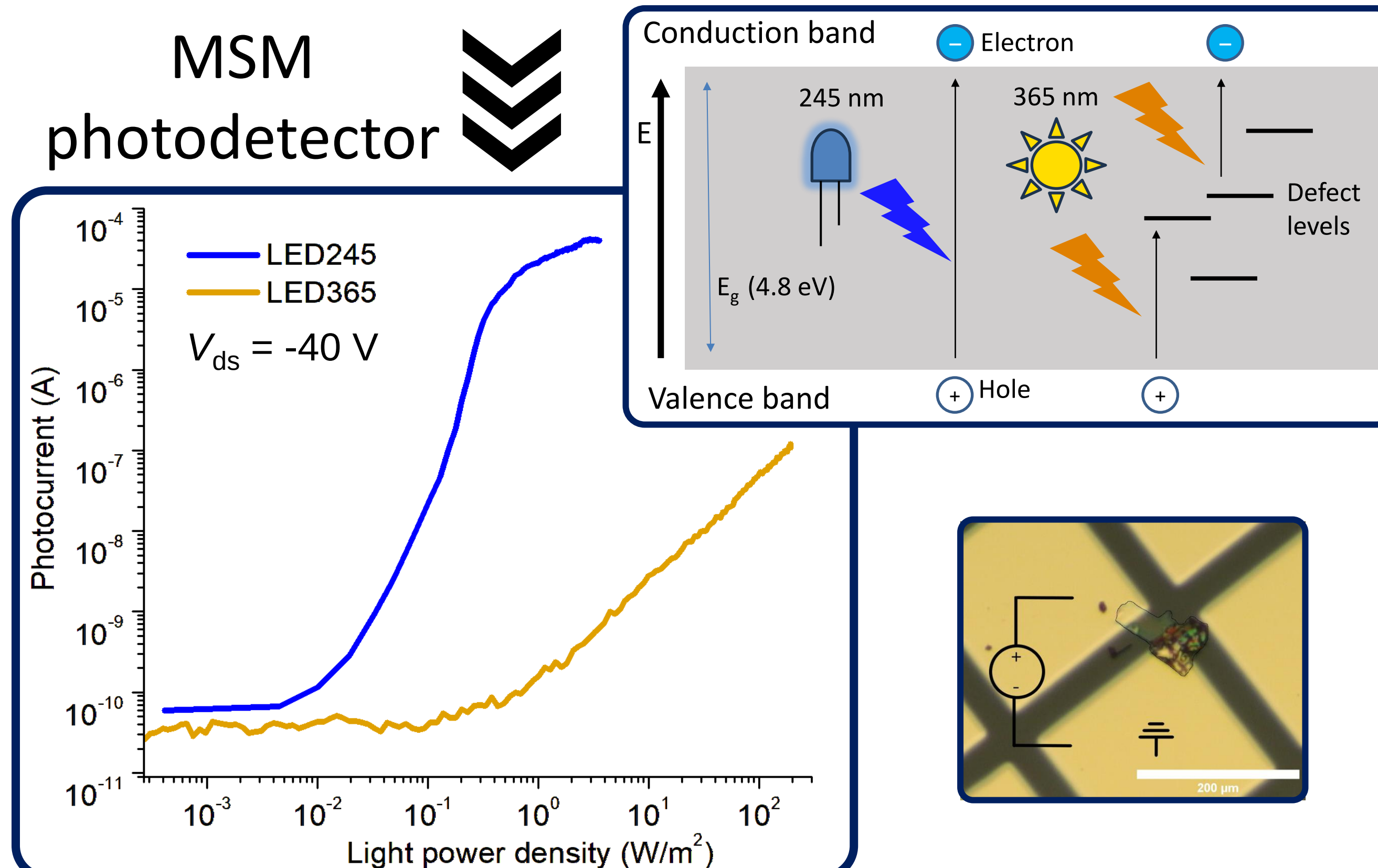
For this, **microfabrication techniques** available at INESC MN and its clean room facilities are employed.

Device structures



Membrane-based MSM photodetectors

- Under illumination** of a **245 nm** wavelength LED (5.1 eV), electrons are excited to the conduction band, resulting in an increase in current;
- Under illumination** of a **365 nm** wavelength LED (3.4 eV), electrons can only be excited indirectly, through defect levels;
- Photocurrent is much higher, at the same power, for above-bandgap excitation, hinting at **solar-blind detection**;
- The **rejection ratio** (R_{245}/R_{365}) is **above 10^5** , for $P_{\text{light}} = 0.7 \text{ W/m}^2$.



Membrane-based phototransistors

- For this phototransistor, **in the dark**, the current can be completely cut for negative gate voltages;
- This effect is much less significant under **245 nm** wavelength illumination;
- The best performance is thus obtained in this configuration, below the threshold voltage, showing **high responsivity and detectivity**.

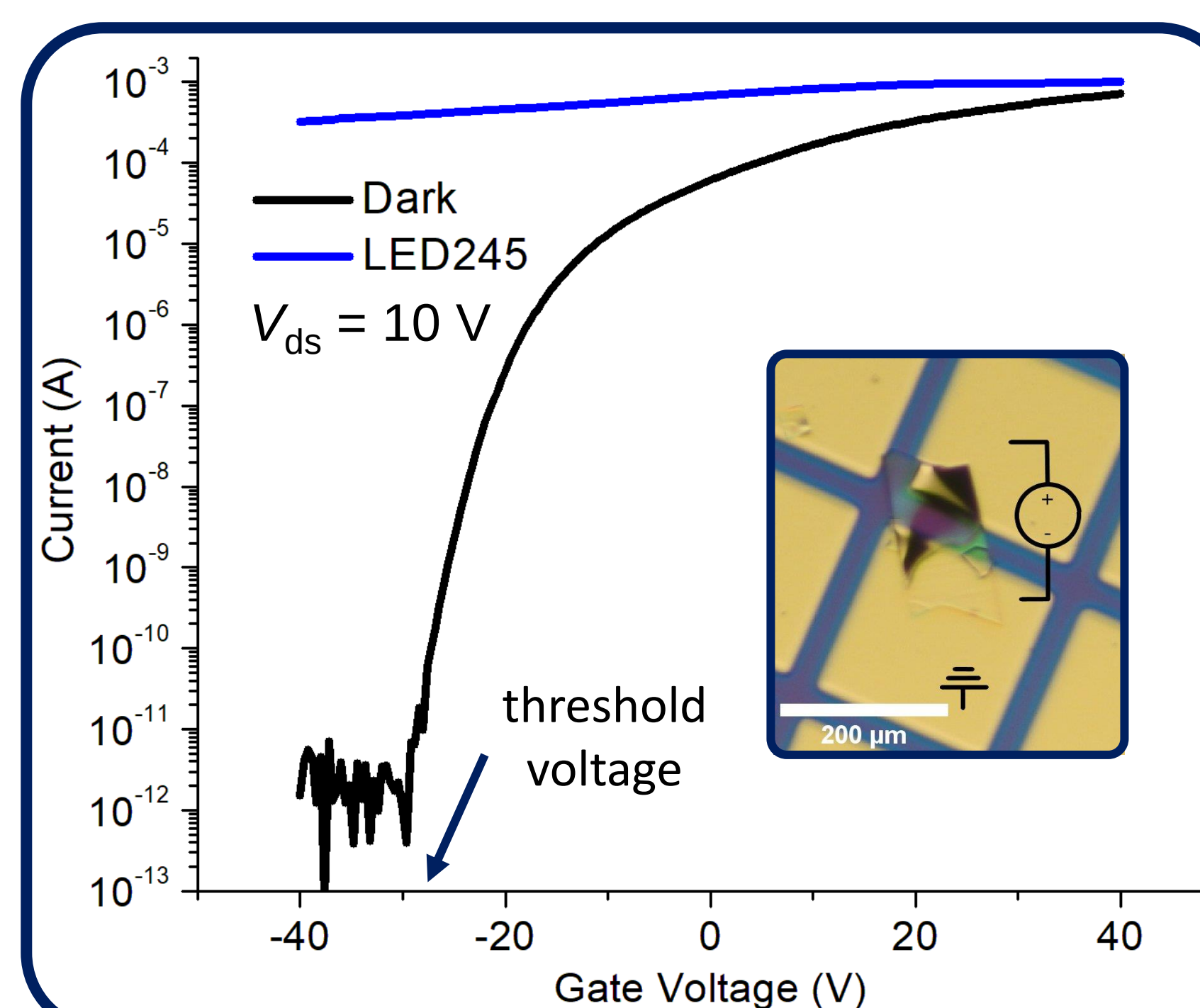


Photo-transistor

The photoresponse can be evaluated using:

$$R = \frac{I_{\text{photo}} - I_{\text{dark}}}{SP_{\text{light}}}$$

$$D = \frac{R\sqrt{S}}{\sqrt{2qI_{\text{dark}}}} \quad (S \text{ is the area of the device})$$

Parameter	Value
R (A/W)	6.6×10^4
D (Jones)	3.8×10^{17}

Future work

- Improving or overcoming the devices' slow recovery after excitation;
- Creating **thinner phototransistors**, possibly with positive threshold voltage, so no energy is required to suppress the dark current;
- Creating **p-n heterojunctions**, between n-type $\beta\text{-Ga}_2\text{O}_3$ membranes and a p-type substrate, such as Si and GaN;
- Characterisation, with **spatial resolution**, of the devices' response, to better understand its mechanisms;
- Taking advantage of the implantation step to introduce optically active ions and create **LEDs of different colours**.